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	THE DIG DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
APPLICATION NO.	94/19/2004	Michael P.C. Watts	P102-44-03	1452	
10/827,118 04/1 25108 7590 MOLECULAR IMPRI	2011 4 1000 5		EXAM	EXAMINER	
	1390		STAICOVIC	STAICOVICI, STEFAN	
KENNETH C.	BROOKS		ART UNIT	PAPER NUMBER	
PO BOX 8153 AUSTIN, TX	6 78708-1536		1732		
Aodin', III			DATE MAILED: 07/14/200	5	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/827,118	WATTS ET AL.				
Office Action Summary	Examiner	Art Unit				
	Stefan Staicovici	1732				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply						
A SHORTENED STATUTORY PERIOD FOR THE MAILING DATE OF THIS COMMUNIC - Extensions of time may be available under the provisions of after SIX (6) MONTHS from the mailing date of this communication of the period for reply specified above is less than thirty (30) or if NO period for reply is specified above, the maximum statures after the serior of the period for reply within the set or extended period for reply will any reply received by the Office later than three months after earned patent term adjustment. See 37 CFR 1.704(b).	ATION. 37 CFR 1.136(a). In no event, however, may a rication. 1 days, a reply within the statutory minimum of thir tory period will apply and will expire SIX (6) MON I, by statute, cause the application to become AB	reply be timely filed ty (30) days will be considered timely. ITHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed	on <u>05 July 2</u> 005.					
<u> </u>						
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims						
4)⊠ Claim(s) <u>1-31</u> is/are pending in the application.						
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>1-31</u> is/are rejected.						
7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/or election requirement.						
Application Papers	, -					
9) The specification is objected to by the Examiner.						
10)⊠ The drawing(s) filed on 19 April 2004 is/are: a)⊠ accepted or b)□ objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11)∐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.						
Priority under 35 U.S.C. § 119						
12)☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).						
a)☐ All b)☐ Some * c)☐ None of:						
1. Certified copies of the priority documents have been received.						
2. Certified copies of the priority documents have been received in Application No						
3. Copies of the certified copies of the priority documents have been received in this National Stage						
application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.						
Attachment(s)	·					
1) Notice of References Cited (PTO-892)	4) 🔲 Interview S	Summary (PTO-413)				
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date						
3) Information Disclosure Statement(s) (PTO-1449 or PT Paper No(s)/Mail Date 8/6/04;6/30/05.	O/SB/08) 5) ☐ Notice of Ir 6) ☐ Other:	nformal Patent Application (PTO-152) 				
J.S. Patent and Trademark Office PTOL-326 (Rev. 1-04)	Office Action Summary	Part of Paper No./Mail Date 20050711				

DETAILED ACTION

Specification

1. The disclosure is objected to because of the following informalities: the instant disclosure includes several references to commonly owned applications. An update on the status of said applications is required.

Appropriate correction is required.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.
- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 3. Claims 1-2, 4-11, 14-16, 18-27 and 29-30 are rejected under 35. U.S.C. 102(b) as being anticipated by Wilson *et al.* (US Patent No. 6,334,960 B1).

Regarding claims 1-2, 4-8 and 11, Wilson et al. ('960) teach the claimed process for forming a pattern on a plate including, providing a mold (40) made form a quartz (material that is transparent to radiation) and having a relief pattern, providing a substrate (10) having a polycarbonate transfer layer (20) (coupling agent) thereon, said transfer layer having an excellent adhesion to a polymerizable material such as, epoxy, polycarbonate or silicone based, that is positioned between said mold (40) and said transfer layer (20). Further, Wilson et al. ('960) teach placing said polymerizable material between said mold and said substrate, transferring said

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pattern from said mold onto said polymerizable material by closing the gap between said mold and said substrate such that said polymerizable material comes into contact with said mold and said substrate, polymerizing said polymerizable material by applying UV radiation and bonding said polymerized material to said transfer layer (see col. 2,line 53 though col. 4, line 63 and Figures1A-1D). Further, Wilson *et al.* ('960) teach that said pattern has an aspect ratio of 0.1-10, wherein the width is about 10nm-5000μm. Hence, it is submitted that the height of the pattern is about 1 nm-500 μm.

In regard to claim 14, Wilson et al. ('960) teach an additional thermal treatment (see col. 4, lines 45-65).

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 12, 28 and 31 are rejected under 35 U.S.C. 103(a) as being unpatentable over Wilson et al. (US Patent No. 6,334,960 B1).

Wilson et al. ('960) teach the basic claimed process as described above.

Regarding claims 12, 28 and 31, although Wilson et al. ('960) teach that the substrate is made from plastics and silicone, Wilson et al. ('960) do not teach that the substrate is made from a radiation transsparent material, such as, quartz. However, Wilson et al. ('960) teach that the mold is made from quartz. Further, Wilson et al. ('960) teach that the material used for making

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the mold and the substrate may be optimized according to the needs of one ordinarily skilled din

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the art. Hence, it is submitted that the material is a result-effective variable. Therefore, it would

have been obvious for one of ordinary skill in the art to have used routine optimization to

determine the material for making the substrate in the process of Wilson et al. ('960) because

Wilson et al. ('960) teach that the material used for making the mold and the substrate may be

optimized according to the needs of one ordinarily skilled din the art, hence teaching that the

mold and substrate material is a result-effective variable and also because quartz is radiation

transparent.

6. Claims 3, 13, 17, 22 are rejected under 35 U.S.C. 103(a) as being unpatentable over

Wilson et al. (US Patent No. 6,334,960 B1) in view of Bailey et al. (US 2002/0115002).

Wilson et al. ('960) teach the basic claimed process as described above.

Regarding claims 3, 13, 17, 22, Wilson et al. ('960) does not teach despositing the

polymerizable material in the form of droplets. Bailey et al. (US 2002/0115002) teaches a fluid

dispensing method of a polymerizable material in an imprint lithographic process including,

forming a pattern of drops between a mold and a support (see paragraph [0126]). Therefore, it

would have been obvious for one of ordinary skill in the art to have provided a pattern of drops

of a polymerizable material as taught by Bailey et al. (US 2002/0115002) in the process of

Wilson et al. ('960) because, Bailey et al. (US 2002/0115002) teaches that such a pattern of

droplets provides for a faster dispensing step, hence reducing production time and as such,

reducing costs.

Conclusion

7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Stefan Staicovici, Ph.D. whose telephone number is (571) 272-1208. The examiner can normally be reached on Monday-Friday 9:30 AM to 6:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael P. Colaianni, can be reached on (571) 272-1196. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Stefan Staicovici, PhD

Primary Examiner